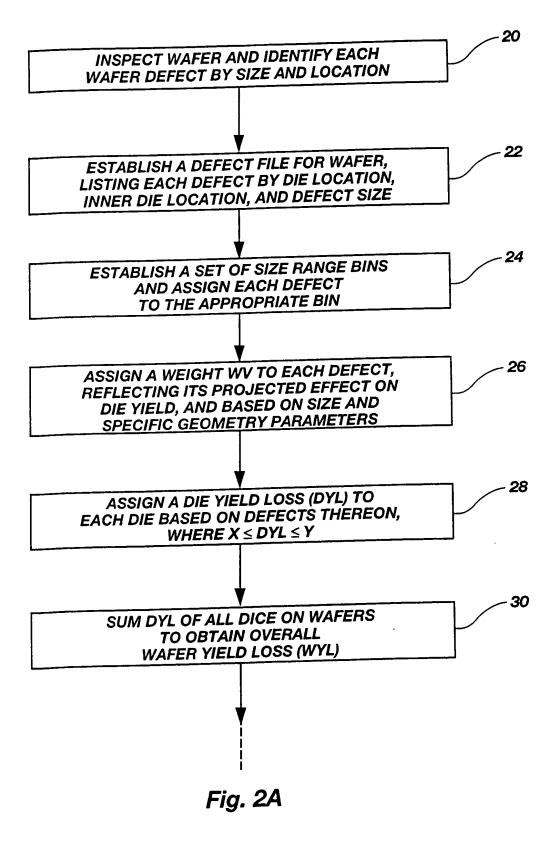
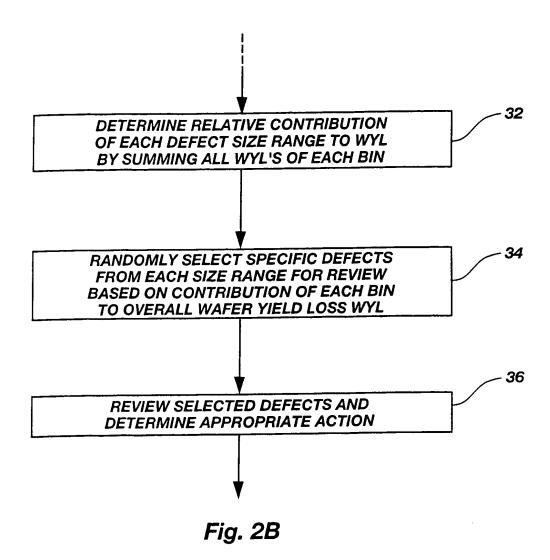


Fig. 1





Lot No. Wäger No. Date Inspection Level

S	0	8	က	0	5	7	12
٩	0.005	0.153	0.216	0.027	0.439	0.159	1.000
Q	0.005	0.141	0.199	0.025	0.404	0.146	0.920
WYL	39.4	34.0	31.7	38.6	23.6	33.8	39.6
% of Total	2.9	46.6	34.0	0.8	10.9	4.6	100.0
# Defects	7	111	81	7	56	11	238
Defect Size	0.0-0.5 µm	0.5-1.0 ит	1.0-2.0 µm	2.0-4.0 µm	4.0-8.0 µm	> 8.0 µm	
Bin No.	1	N	8	4	ર	9	Total

Fig. 3

## **DEFECT REVIEW SHEET**

PART TYPE:

DATE:

# DEFECTS SAMPLED:

LOT NO: WAFER ID: STEP ID: TOOL ID:

PROJECT NO:

OPERATOR: TIME IN: TIME OUT:

PREDICTED WAFER YIELD LOSS WYL + 39.6 TOTAL DEFECT COUNT = 238

BIN # 1		2		3		4		5	5			6				
SIZE	0.0-0.5		0.5-1.0		1.0-2.0		2.0-4.0		4.0-8.0			> 8.0		_		
WYL	YL   39.4		34.0		31.7		38.6		23.6			33.8				
# DEFECTS	7		111		81		2		2	26		11				
	ID	P	ID	P		ID	P		ID	P	ID	P		ID	P	
			183	2	Īν	64	2	Īν			13	1	V	162	1	K
			213	2	V	205	2	V	/		83	1	V	192	1	K
					$\mathbf{I}$	226	2	N			194	1	Ţ			Γ
								П			206	2	V			Γ
								П			225	2		,		Γ

EXTRA SAMPLES								
DIE	DEFECT ID	DESCRIPTION						

DEFECT TYPE	DESCRIPTION	TOTAL
1	Block etch	5
2	Lower Level Contamination	7
3		
4		
5		
6	CANNOT FIND	

Fig. 4